



## A. Interconnect & Package 분과

2021년 1월 27일(수), 14:45-16:15 / 채널 C

### [WC4-A] Emerging Interconnect II

좌장: 김병준 교수 (안동대학교), 이웅선 수석 (SK하이닉스)

<p><b>WC4-A-1</b> 14:45-15:15</p>	<p>[초청] <b>Mechanism of Selective Cobalt Capping Process for Copper Interconnects: A DFT Study</b> Romel Hidayat<sup>1</sup>, Tanzia Chowdhury<sup>1</sup>, Hye-Lee Kim<sup>1</sup>, Sang-Ick Lee<sup>2</sup>, and Won-Jun Lee<sup>1</sup> <sup>1</sup>Departments of Nanotechnology and Advanced Materials Engineering, Sejong University, <sup>2</sup>DNF Co., Ltd.</p>
<p><b>WC4-A-2</b> 15:15-15:30</p>	<p><b>Effect of Complexing Agents on Co Surface Modification for Chemical-Mechanical Polishing (CMP) and Post-CMP Cleaning Process</b> Jinuk Byun<sup>1</sup>, Ohsung Kwon<sup>2</sup>, Kyong Kyu Myong<sup>1</sup>, KiHo Bae<sup>3</sup>, and Jae Jeong Kim<sup>1,4</sup> <sup>1</sup>School of Chemical and Biological Engineering, Seoul National University, <sup>2</sup>Department of Chemical and Biomolecular Engineering, University of Illinois at Urbana-Champaign, <sup>3</sup>Semiconductor R&amp;D Center, Samsung Electronics Co., Ltd., <sup>4</sup>School of Chemical and Biological Engineering, Institute of Chemical Process, Seoul National University</p>
<p><b>WC4-A-3</b> 15:30-15:45</p>	<p><b>Mechanical Planarization of Polymer Dielectrics for FOWLP</b> Hyeokjin Chu<sup>1</sup>, Hyunjoo Kim<sup>2</sup>, and Sungdong Kim<sup>1</sup> <sup>1</sup>Department of Mechanical System Design, Seoul National University of Science and Technology, <sup>2</sup>Department of Chemistry &amp; Biology, Seoul National University of Science and Technology</p>
<p><b>WC4-A-4</b> 15:45-16:00</p>	<p>철회</p>
<p><b>WC4-A-5</b> 16:00-16:15</p>	<p><b>Mechanism of Grain Size and Mechanical Properties of Sn-57.6Bi-0.4Ag Solder Joint by Using the Nanoindentation</b> Jun-Ho Jang, Kyung Deuk Min, Choong-Jae Lee, Jae-Ha Kim, Dong Gil Kang, and Seung-Boo Jung School of Advanced Materials Science and Engineering, Sungkyunkwan University</p>

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